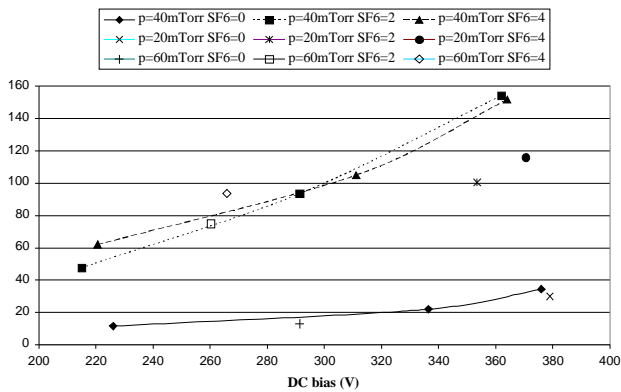
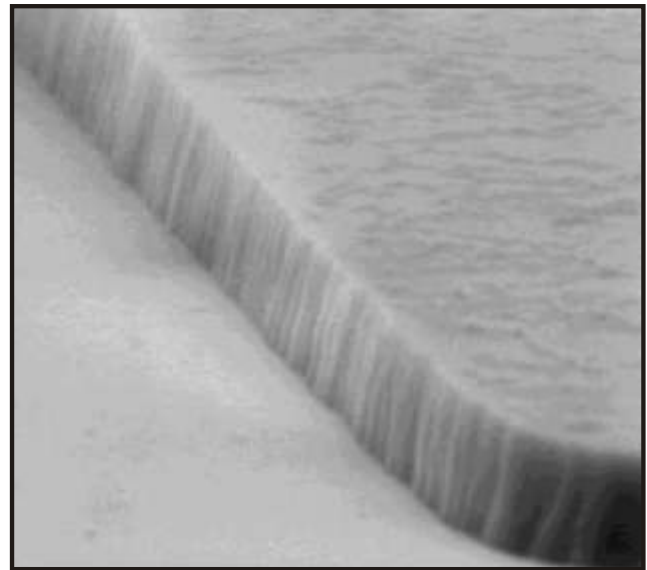
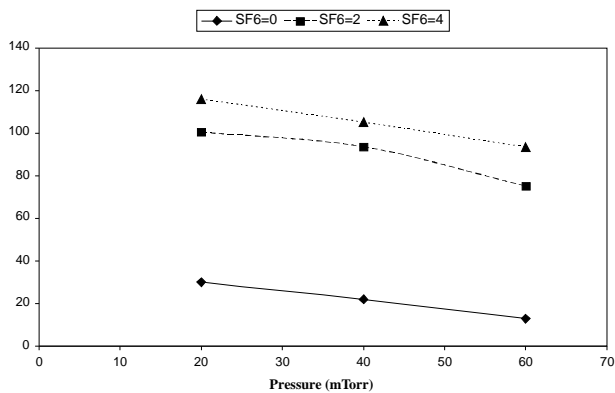


Plasmalab Data

GaN RIE



Etch rate in nm/ min vs power and bias

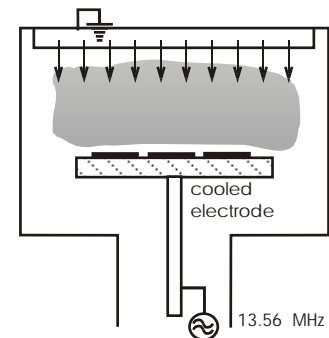


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www.ele.tue.nl/~tte/devices/index.html

Plasmalab 80 Plus

Plasmalab System 100

Plasmalab System 133



Technology:
 Parallel Plate Configuration
 RIE-Mode (13.56 MHz)
 Cl/F - Process

Results:
 Rate : 50 - 150 nm/ min
 Selectivity to PECVD - SiN 5 : 1
 Profile: anisotropic